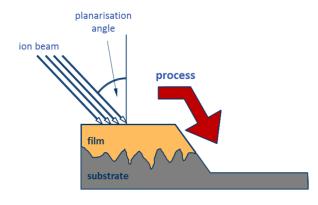
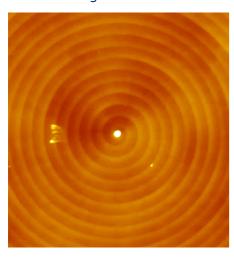
ION BEAM ASSISTED SURFACE SMOOTHING

THE INSTITUTE



- Use of ion beams for surface smoothing down 0.1 nm rms
- Techniques: ion beam direct smoothing, ion beam planarization, thin film deposition
- Application: removal of tool marks after diamond turning





The Leibniz Institute of Surface Engineering (IOM) is well known for its competence and excellence in engineering surfaces and thin films by ion beam, electron, laser and plasma techniques. The

institute performs application-oriented basic research by aiming for scientific knowledge gain related to the physical and chemical mechanisms in the preparation, synthesis and modification of insulating, metallic, semiconducting and polymeric surfaces and thin films. One of the main objectives of the institute is to transfer its scientific understanding to product- and method-oriented applications useful to industrial partners who wish to use engineered materials and surfaces in economically relevant and forward-looking technology fields.

Leibniz Institute of Surface Engineering (IOM)

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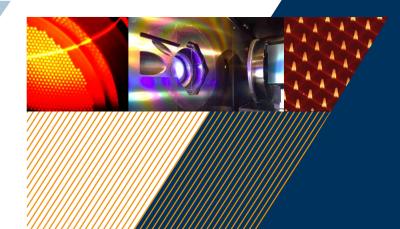
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IOM APPLICATION CENTER: ION BEAM ASSISTED TECHNOLOGIES



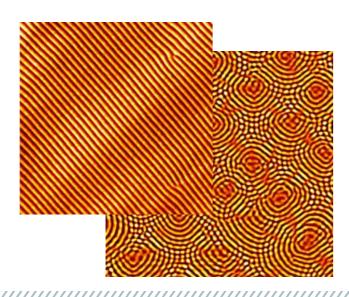
ION BEAM DRIVEN SELF-ORGANIZATION

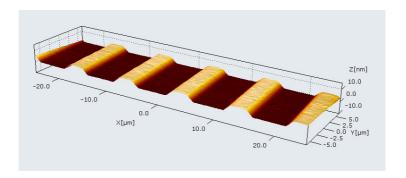
(R)IBE FOR PATTERN TRANSFER

IBE/RIBE ON LARGE SURFACES



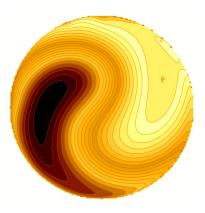
- Application of ion beam assisted self-organization processes for nanopatterning of surfaces
- Simple and cost efficient method
- Tested materials: Si, Ge, SiO₂, Al₂O₃, III-V-semiconductors, metals, etc.





- Reactive and non-reactive etching technologies
- Structure depth from 50 pm up to 10 μm
- Materials: Si, fused silica, different glasses, Zerodur, semiconductors, optical layer systems, etc.





- Modern machinery for IBE/RIBE processes (patterning, smoothing, etc.)
- Development of sophisticated motion algorithms for IBE/RIBE
- Application: uniform etching processes up to 500 mm in diameter

